

Title (en)

Bright nickel plating bath and process and composition therefor.

Title (de)

Bad zum Glanzvernickeln und Verfahren und Zusammensetzung hierfür.

Title (fr)

Procédé et bain pour nickelage brillant et composition à cet effet.

Publication

**EP 0025694 A1 19810325 (EN)**

Application

**EP 80303183 A 19800910**

Priority

US 7495379 A 19790913

Abstract (en)

Plating defects may occur during the electrodeposition of nickel using compositions containing primary and secondary brighteners. According to the invention such defects are avoided by including 0.01 to 1 g/l of a sulfonated acetylenic compound or a salt of such a compound in an aqueous acidic nickel plating bath containing 0.2 to 10 g/l of saccharin, and 20 to 500 parts per million of Zn ions. The acetylenic bond and the sulfonate radical of the sulfonated acetylenic compound are connected by a carbon chain of at least one carbon atom and not more than 6 carbon atoms. The invention relates to the composition of such a bath, to the method of bright nickel plating using such a bath and to compositions for forming the bath.

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CPC (source: EP)

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Citation (search report)

- DE 2654040 A1 19770608 - MCGEAN CHEMICAL CO
- DE 2460247 A1 19750710 - DU PONT
- GB 1456583 A 19761124 - OXY METAL INDUSTRIES CORP
- GB 1441972 A 19760707 - OXY METAL FINISHING CORP
- US 4016051 A 19770405 - GELDZAHLER CHARLES, et al
- US 3884773 A 19750520 - MERKER REUVEN, et al

Cited by

EP3680366A4; GB2189258B; US11821099B2; WO2018015168A1; EP3885475A1

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